

REMARKS

Claims 1-19 are pending. The Examiner's reconsideration of the rejections is requested in view of the remarks.

Claims 1, 9, and 14 are the independent claims.

Claims 1-4 have been rejected under 35 U.S.C. 102(e) as being unpatentable over Isobe et al. (U.S. Patent Application No. 2003/0218169). The Examiner stated essentially that Isobe teaches or suggests all the limitations of Claims 1-4.

Claim 1 claims, *inter alia*, "disposing a mask including a pattern shape over the layer formed on a substrate; and scanning the mask with the light, such that a direction of the scanning is substantially perpendicular to a longitudinal direction of the pattern shape to form a pattern."

Isobe teaches determining a scanning path based on an insulating film pattern and a width in the direction perpendicular to the laser beam scanning direction (see paragraphs [0029] and [0092]). Isobe does not teach "scanning the mask with the light, such that a direction of the scanning is substantially perpendicular to a longitudinal direction of the pattern shape to form a pattern" as claimed in Claim 1. Isobe merely teaches that a scanning direction of the laser and a width of the laser are determined (emphasis added)(see paragraph [0034]). Nowhere does Isobe teach that the scanning direction is perpendicular to a direction of a pattern shape. The scanning direction of Isobe is parallel to the direction of the projection portion (see paragraph [0081 and Figure 2A]). Further, Isobe does not teach that the depression portion nor the projection portion are analogous to a "longitudinal direction of the pattern shape" as claimed in Claim 1. Even assuming *arguendo* that the depression portion or projection portion are analogous to a longitudinal direction of the pattern shape, the travel of the laser is parallel thereto. Therefore, Isobe does not teach "scanning the mask with the light, such that a direction of the scanning is

substantially perpendicular to a longitudinal direction of the pattern shape to form a pattern” as claimed in Claim 1. Therefore, Isobe fails to teach all the limitations of Claim 1.

Claims 2-4 depend from Claim 1. The dependent claims are believed to be allowable for at least the reasons given for Claim 1.

Claims 5, 6, and 8 have been rejected under 35 U.S.C. 103(a) as being unpatentable over Isobe in view of Kim (U.S. Patent Application No. 2003/0211404). The Examiner stated essentially that the combined teachings of Isobe and Kim teach of suggest all the limitations of Claims 5, 6, and 8.

Claims 5, 6, and 8 depend from Claim 1. The dependent claims are believed to be allowable for at least the reasons given for Claim 1. Reconsideration of the rejection is respectfully requested.

Claim 7 has been rejected under 35 U.S.C. 103(a) as being unpatentable over Isobe in view of Tanuma et al. (USPN 5,718,839). The Examiner stated essentially that the combined teachings of Isobe and Tanuma teach of suggest all the limitations of Claim 7.

Claim 7 depends from Claim 1. Claim 7 is believed to be allowable for at least the reasons given for Claim 1. Reconsideration of the rejection is respectfully requested.

Claims 9, 10, 14, 15, and 19 have been rejected under 35 U.S.C. 103(a) as being unpatentable over Isobe in view of Yang (U.S. Patent Application No. 2003/0213966). The Examiner stated essentially that the combined teachings of Isobe and Yang teach of suggest all the limitations of Claims 9, 10, 14, 15, and 19.

Claim 9 claims, *inter alia*, “scanning the mask with a light, such that a direction of the scanning is substantially perpendicular to a longitudinal direction of the pattern shape to expose the photoresist layer.” Claim 14 claims, *inter alia*, “forming a photosensitive layer pattern by

scanning with a light through a mask, wherein a direction of scanning is substantially perpendicular to a longitudinal direction of a data line to be formed during an exposure process, and the photosensitive layer pattern includes a first portion, a second portion thicker than the first portion, and a third portion thinner than the first portion.”

Yang teaches a process for vapor depositing a low dielectric insulating film (see Abstract). As noted in the Office Action, Yang does not disclose scanning substantially perpendicular to a longitudinal direction of the pattern shape to expose the photoresist layer. Nowhere does Yang does not teach or suggest “scanning the mask with a light, such that a direction of the scanning is substantially perpendicular to a longitudinal direction of the pattern shape to expose the photoresist layer” as claimed in Claim 9, nor “forming a photosensitive layer pattern by scanning with a light through a mask, wherein a direction of scanning is substantially perpendicular to a longitudinal direction of a data line to be formed during an exposure process” as claimed in Claim 14. Therefore, Yang fails to teach or suggest all the limitations of Claims 9 and 14.

Isobe teaches determining a scanning path based on an insulating film pattern and a width in the direction perpendicular to the laser beam scanning direction (see paragraphs [0029] and [0092]). Isobe does not teach or suggest “scanning the mask with a light, such that a direction of the scanning is substantially perpendicular to a longitudinal direction of the pattern shape to expose the photoresist layer” as claimed in Claim 9, nor “forming a photosensitive layer pattern by scanning with a light through a mask, wherein a direction of scanning is substantially perpendicular to a longitudinal direction of a data line to be formed during an exposure process” as claimed in Claim 14. Isobe merely teaches that a scanning direction of the laser and a width of the laser are determined (emphasis added). The scanning direction of Isobe is parallel to the

direction of the projection portion (see paragraph [0081 and Figure 2A]). Nowhere does Isobe teach or suggest that the scanning direction is perpendicular to a direction of a pattern shape. Therefore, Isobe fails to cure the deficiencies of Yang.

The combined teachings of Yang and Isobe fail to teach or suggest “scanning the mask with a light, such that a direction of the scanning is substantially perpendicular to a longitudinal direction of the pattern shape to expose the photoresist layer” as claimed in Claim 9, nor “forming a photosensitive layer pattern by scanning with a light through a mask, wherein a direction of scanning is substantially perpendicular to a longitudinal direction of a data line to be formed during an exposure process” as claimed in Claim 14. Therefore, the combined teachings of Yang and Isobe fail to teach or suggest all the limitations of Claims 9 and 14.

Claim 10 depends from Claim 9. Claims 15 and 19 depend from Claim 14. The dependent claims are believed to be allowable for at least the reasons given for Claims 9 and 14. Reconsideration of the rejection is respectfully requested.

Claims 11 and 16 have been rejected under 35 U.S.C. 103(a) as being unpatentable over Yang in view of Isobe and further in view of Tanuma. The Examiner stated essentially that the combined teachings of Yang, Isobe, and Tanuma teach or suggest all the limitations of Claims 11 and 16.

Claims 11 and 16 depend from Claims 9 and 14, respectively. The dependent claims are believed to be allowable for at least the reasons given for Claims 9 and 14. Reconsideration of the rejection is respectfully requested.

Claims 12, 13, 17, and 18 have been rejected under 35 U.S.C. 103(a) as being unpatentable over Yang in view of Isobe and further in view of Kim. The Examiner stated

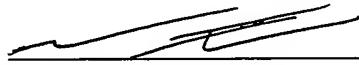
essentially that the combined teachings of Yang, Isobe, and Kim teach of suggest all the limitations of Claims 12, 13, 17, and 18.

Claims 12 and 13 depend from Claim 9. Claims 17 and 18 depend from Claim 14. The dependent claims are believed to be allowable for at least the reasons given for Claims 9 and 14. Reconsideration of the rejection is respectfully requested.

For the forgoing reasons, the present application, including Claims 1-19, is believed to be in condition for allowance. The Examiner's early and favorable action is respectfully urged.

Respectfully submitted,

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